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Sheet 1 of 1



INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Attorney Docket No. 2285/51302	Serial No. 10/052,306
		Applicant: Yumiko KAWANO, et al.	
		Filing Date January 18, 2002	Group

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	TRANSLATION	
							Yes	No
ER	AK	64-501	01/1989	Japan				No
ER	AL	0349695	01/90	L'Air Liquide				No
	AM	63-072881	04/88	Toshiba Corporation				Abstract
	AN	09-186110	07/97	Tokyo Electron				Abstract
	AO	05-078846	03/93	Osaka Gas Co.				Abstract
ER	AP	05-226282	09/1993	NEC Corporation				Abstract
ER	AQ	64-068474	09/1989	Tokyo Electron				Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

CK	AR	S.C. SUN, et al. "Characterization of Diffusion Barrier Properties of CVD and PVD Tungsten Nitride Thin Films" VMIC Conference, June 18-20, 1996				
ER	AS	Toshiya SUZUKI, et al., "Comparison of CVD TiN, PECVD WN _x , and CVD W-Si-N as Upper Electrode Materials for Ta ₂ O ₅ DRAM Capacitors" Conference Proceedings ULSI XIII, 1998				
	AT					

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

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